

ABSTRACT OF THE DISCLOSURE

A method of manufacturing the reticles for manufacturing a semiconductor product using a photolithographic process is relatively error free and can be carried out time in a short amount of time. The method includes creating a first database, in which data of coordinates, regions and process execution conditions for a plurality of pattern images to be transcribed onto various types of semiconductor products, is classified into respective product groups each containing similar ones of the products, creating a second database of process marks and scribe lane regions corresponding to each of the classified product groups; extracting from the second database data for the process mark and scribe lane region of a reticles for manufacturing the product; determining reference coordinates for the process mark based on reference coordinates of the plurality of pattern images and the selected scribe lane region; and designing and forming a reticle through batch-process between the coordinates of the process mark and the reference coordinates of the pattern images.